plates and the electric-connecting coupling hole and the non-electric-connecting coupling hole are alternately arranged,

a spacer installed between the adjacent electrode plates, and

an electric-conductive coupler which is inserted through an array of the electric-connecting coupling hole and the non-electric-connecting coupling hole to couple the electrode plates together, and is caught into contact with the shoulder to be electric-connected with the electrode,

wherein electricity is applied through the electric-conductive coupler to the electrode to generate a plasma discharge.

6. (Original) The plasma reactor as claimed in claim 5,

wherein the electric-conductive coupler comprises plural coupler elements joined together in an axial direction, each coupler element consisting of single body.

7. (Original) The plasma reactor as claimed in claim 6,

wherein the coupler element has an electric-connecting part inserted into the electric-connecting coupling hole and the gap over the electric-connecting coupling hole, a non-electric-connecting part inserted into the non-electric-connecting coupling hole and the gap over the non-electric-connecting coupling hole, and a joining part joining the coupler elements together for more than two electrode plate to be stacked.

8. (Original) The plasma reactor as claimed in claim 7,

wherein the coupler element is formed such that the joining part is on the opposite side of the non-electric-connecting part from the electric-connecting part;

the electric-connecting part has a larger outer diameter than the non-electric-connecting part and the non-electric-connecting part has either a larger outer diameter than the joining part or as large an outer diameter as the joining part;

the electric-connecting part has a shoulder corresponding to the shoulder of the electric-connecting coupling hole; and

the joining part has a male thread on an outer surface and the electric-connecting part correspondingly has a female threaded hole, the joining part being inserted into the female

threaded hole of the electric-connecting part of another adjacent coupler element so that the coupler elements are joined together.

9. (Original) The plasma reactor as claimed in claim 5,

wherein the electric-conductive coupler includes a coupling shaft and a wing which are joined together;

the coupling shaft consists of single body and is inserted through an array of the electric-connecting coupling hole and the non-electric-connecting coupling hole which are alternately arranged; and

the wing is joined to an outer surface of the coupling shaft and is caught into contact with the shoulder of the electrode plate.

10. (Original) The plasma reactor as claimed in claim 9,

wherein the wing has a through hole at its center into which the coupling shaft is inserted and a lateral opening which extends in the radial direction from the through hole, and

the coupling shaft has a large outer diameter part onto which the wing is joined and a small outer diameter part whose diameter is smaller than a width of the lateral opening.

11. (Original) The plasma reactor as claimed in claim 10,

wherein the large outer diameter part is inserted into the electric-connecting coupling hole and the gap over the electric-connecting coupling hole;

the small outer diameter part is inserted into the non-electric-connecting coupling hole and the gap over the non-electric-connecting coupling hole; and

the spacer inserted into the gap over the non-electric-connecting coupling hole has a through hole with a larger inner diameter than the outer diameter of the large outer diameter part.

12. (Original) The plasma reactor as claimed in claim 10,

wherein the coupling shaft has a male thread on an outer surface of the large outer diameter part and the wing has a female thread on an inner surface of the through hole, the coupling shaft and the wing are joined together in a screwed type.

13. (Currently amended) The plasma reactor as claimed in claim 5,

wherein the electrode plate comprises a first dielectric sheet plate and a second dielectric sheet plate, the first dielectric sheet plate having the electrode on one surface onto which the second dielectric sheet plate is bonded;

the first dielectric sheet plate has the electric-connecting coupling hole with a small diameter which contacts with the electrode and the non-electric-connecting coupling hole with a small diameter;

the second dielectric sheet plate has the electric-connecting coupling hole with a large diameter and the non-electric-connecting coupling hole with a small diameter; and

the first dielectric sheet plate and the second dielectric sheet plate are bonded together such that the electric-connecting coupling holes and the non-electric-connecting coupling holes are arranged in line respectively.

14. (Original) The plasma reactor as claimed in claim 5,

wherein the electric-conductive coupler includes a coupling shaft and a medium, the coupling shaft consisting of single body and being inserted through an array of the electric-connecting coupling hole and the non-electric-connecting coupling hole which are alternately arranged, the medium contacting with an outer surface of the coupling shaft and the shoulder of the electrode plate at the same time.

15. (Original) The plasma reactor as claimed in claim 14,

wherein the electrode plate comprises a first dielectric sheet plate and a second dielectric sheet plate, the first dielectric sheet plate having the electrode on one surface onto which the second dielectric sheet plate bonded;

the first dielectric sheet plate has the electric-connecting coupling hole with a small diameter which contacts with the electrode and the non-electric-connecting coupling hole with a large diameter;

the second dielectric sheet plate has the electric-connecting coupling hole with a large diameter and the non-electric-connecting coupling hole with a small diameter; and

the first dielectric sheet plate and the second dielectric sheet plate are bonded together such that the electric-connecting coupling holes and the non-electric-connecting coupling holes are arranged in line respectively.

16. (Original) The plasma reactor as claimed in claim 14,

wherein the medium is an electric-conductive bushing.

17. (Original) The plasma reactor as claimed in claim 14,

wherein the non-electric-connecting coupling hole has a shoulder facing opposite to the shoulder of the electric-connecting coupling hole.

18. (Original) The plasma reactor as claimed in claim 17,

wherein a non-electric-conductive bushing is installed into contact with an outer surface of the coupling shaft and the shoulder of the non-electric-connecting coupling hole.

19. (Previously presented) The plasma reactor as claimed in claim 16, wherein the spacer has a through hole into which the coupling shaft is inserted to encompass an outer surface of the coupling shaft, and has a recess in a place facing the shoulder, and

the bushing is inserted between the recess and the shoulder.

20. (Previously presented) The plasma reactor as claimed in claim 5, wherein the shoulder is a circular step which is formed by a change of an inner diameter of the coupling hole.

21. (Previously presented) The plasma reactor as claimed in claim 5, wherein the electrode plate comprises a first dielectric sheet plate and a second dielectric sheet plate which are bonded together such that the electrode is located between the first dielectric sheet plate and the second dielectric sheet plate, and

the first dielectric sheet plate and the second dielectric sheet plate is bonded with a ceramic paste.

22. (Previously presented) The plasma reactor as claimed in claim 5, wherein the spacer has a through hole into which the electric-conductive coupler is inserted, the through hole encompassing an outer surface of the electric-conductive coupler.

23. (Previously presented) The plasma reactor as claimed in claim 5, wherein the spacer is made of a glass fiber.

24. (Previously presented) The plasma reactor as claimed in claims 5, wherein a part of the electric-conductive coupler inserted into the non-electric-connecting coupling hole has a smaller outer diameter than an inner diameter of the non-electric-connecting coupling hole, and

the spacer corresponding to the non-electric-connecting coupling hole has a prominent bushing part which is inserted between the non-electric-connecting coupling hole and the electric-conductive coupler.

25. (Previously presented) The plasma reactor as claimed in claim 5, wherein a washer is inserted between the shoulder of the electrode plate and the electric-conductive coupler.

26. (Previously presented) The plasma reactor as claimed in claim 5, wherein an outward exposed part of the electric-conductive coupler inserted through an array of the coupling holes on one side is covered with an insulating cap to insulate and fix the electric-conductive coupler, and

the electric-conductive coupler installed through an array of the coupling holes on the other side is grounded.

27. (Previously presented) The plasma reactor as claimed in claim 5, wherein the electrode has a hole surrounding part which surrounds the electric-connecting coupling hole, a discharging part which is formed widely on an area corresponding to the discharge space, and a connecting neck part which is formed narrowly and connects the hole surrounding part with the discharging part, and

the hole surrounding part has the same radial width as an exposed part of the shoulder.

28. (Currently amended) The plasma reactor as claimed in claim 5, wherein an outer surface of dielectric member exposed to the discharge space is coated with a predetermined porosity reduction material ~~the electrode plate is the electrode plate according to claims 1~~.

29. (Currently amended) [[A]]The plasma reactor ~~comprising:~~ as claimed in claim 28, wherein the dielectric member includes a plurality of dielectric sheet plates, and the electrode plate is formed by bonding together the dielectric sheet plates with a porosity reduction material, at least one dielectric plate having the electrode on a surface facing another dielectric sheet palate

~~more than two electrode plates, each electrode plate including a dielectric member and an internal electrode protected by the dielectric member,~~

~~a guide structure separably supporting the electrode plates in such a manner that the electrode plates are stacked apart from each other,~~

~~wherein the electrodes of the electrode plates stacked apart from each other are connected alternately with the two poles of an electric source and electricity is applied to the electrodes to generate a plasma discharge.~~

30. (Currently amended) The plasma reactor as claimed in claim 29, wherein the porosity reduction material is a glass paste.

~~wherein the guide structure has slide slots into which the electrode plates are inserted to be stacked~~.

31. (Cancelled)